



ICRP-12/SPP-44

12th International Conference on Reactive Plasmas
44th Symposium on Plasma Processing

Date : 30 November-3 December 2026

Venue : KANAZAWA BUNKA HALL

International Organizing Committee Chair:
Tatsuru Shirafuji (Osaka Metropolitan University)

Local Organizing Committee Chair:
Yasunori Tanaka (Kanazawa University)

Important Dates

Abstract Submission Opens	Apr. 15 (Wed.)
Registration Opens	Jun. 1 (Mon.)
Abstract Submission Deadline	Jun. 30 (Tue.)
Abstract Acceptance Notification	Late July
Early-bird Registration Deadline	Sep. 30 (Wed.)

Secretariat of ICRP-12/SPP-44

c/o PCO, Inc.
2-25 Sakurabashi-dori,
Toyama-shi, Toyama 930-0004, Japan
E-mail:icrp12@pcojapan.jp

Website: <https://smartconf.jp/content/icrp-12>

Co-sponsored by

Plasma Electronics Division,
The Japan Society of Applied Physics



ICRP-12/SPP-44



General Information

The International Conference on Reactive Plasmas (ICRP) has taken place by the initiative of the Division of Plasma Electronics, the Japan Society of Applied Physics since 1991. The 1st ICRP was held in Nagoya, the 2nd in Yokohama (1994), the 3rd in Nara (1997), and the most recent conference (11th ICRP) in Sendai (2022). Some former ICRPs were held as international joint conferences: the 4th ICRP was with the Gaseous Electronics Conference (GEC) at Maui in 1998, the 5th was with ESCAMPIG at Grenoble (2002), the 7th was with GEC at Paris in 2010, 9th was with GEC at Honolulu in 2015, 10th was with International Conference on Phenomena in Ionized Gases (ICPIG) at Sapporo in 2019, and 11th was with GEC at Sendai in 2022.

The Symposium on Plasma Processing (SPP) is a domestic annual Japanese meeting that has been held by the Division of Plasma Electronics since 1984. The joint ICRP and SPP conference aims to gather researchers and engineers, involved in various aspects of reactive plasmas and their applications. The joint conference also aims to facilitate the exchange of information and ideas among them within an international framework.

The subjects covered in this conference are the entire field of reactive plasmas and their applications to various materials processing such as surface modification, etching and deposition with emphasis on basic phenomena, technologies, and the underlying basic physics and chemistry. Furthermore, the subjects have been extended to biological, agricultural, and medical application of plasmas. This conference particularly encourages papers dealing with basic properties of the plasma itself, its generation and control, fundamental processes in the plasma, and plasma-solid/liquid interactions. Papers dealing with specific results of processing should place emphasis on the related plasma characteristics in obtaining the results.

The 12th ICRP will take place in November 30-December 3, 2026, in Kanazawa, Japan. This conference will also be held as a joint conference with the 44th Symposium on Plasma Processing. The conference site will be at Kanazawa Bunka Hall.

Call For Paper

Authors are required to submit a manuscript (up to two pages, A4 size) for ICRP proceedings volume (in a two-column, camera-ready form). Further details and a template will be available at the conference website.

Program

Plenary Speakers



Prof. Hirotaka Toyoda
(Nagoya University, Japan)



Prof. Bruce R. Lock
(Florida State University, USA)

Conference Topics

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| 1. Production and Control of Low Pressure Reactive Plasmas | 7. Etching |
| 2. Production and Control of Atmospheric Pressure and Thermal Plasmas | 8. Deposition |
| 3. Production and Control of Liquid-Phase and Gas-Liquid Interface Plasmas | 9. Surface Modification |
| 4. Diagnostics, Measurement and Monitoring of Reactive Plasmas | 10. Applications for Nanotechnology |
| 5. Elementary Processes in Reactive Plasmas | 11. Applications for Environment and Energy |
| 6. Modeling and Simulation in Reactive Plasmas | 12. Applications for Life Sciences |
| | 13. Applications for Propulsion and Aerodynamics |
| | 14. New Trends of Reactive Plasmas / Emerging Technologies |

Special Session

- S1. Special Session on Data Driven Reactive Plasma Science and Technology
- S2. Special Session on Plasma Seed Science
- S3. Special Session on Diamond and Related Material Process and Applications

Social Events

► Welcome Reception

Date: Nov.29, 2026

Venue: Kanazawa Bunka Hall

► Banquet

Date: Dec. 2, 2026

Venue: Gojukken Nagaya, the 50-Bay Long Storehouse

Fee: 10,000 JPY (tentative) (Banquet fee is not included in conference registration)

Venue & Access

(Further details are available on the conference website.)

